

Notice of References Cited

Application/Control No.

10/765,366

Applicant(s)/Patent Under

Reexamination

KIM ET AL.

Examiner

ANGELA BERTAGNA

Art Unit

1637

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U.S. PATENT DOCUMENTS

*	Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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NON-PATENT DOCUMENTS

*	Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
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